FORM PTO - 1449

SUPPLEMENTAL INFORMATION P E DISCLOSURE STATEMENT

ATTY DOCKET NO.:

ASC-025DV1C1

APPLICANT(S):

Cheng et al.

SERIAL NO.:

10/802,185

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			HOV T 5	MARIE	GROUP:		281	3		.,,,
			U.	S. PATEN	NT DOCUM	MENTS				
XAM. VIT.		DOCUMENT NUMBER	DATE	NAME			CLASS	SUB CLASS	1	LING DATE IF
41	A236	4,969,031	11/00/1990	Kobayas	shi <i>et al</i> .					
AT	A237	5,439,843	08/08/1995	Sakaguc	hi <i>et al</i> .					
CAT	A238	5,548,128	08/20/1996	Soref et	al.					
AT	A239	5,607,876	03/04/1997	Biegelse	en et al.					
AT	A240	6,489,639	12/03/2002	Hoke et	al.					
M	A241	6,591,321	07/08/2003	Arimilli	et al.				11	/09/1999
AT	A242	6,597,016	07/22/2003	Yuki et	al.				01	/13/2000
M	A243	6,646,322	11/11/2003	Fitzgera	ld				07	7/16/2001
M	A244	6,674,150	01/06/2004	Takagi e	et al.				04	1/23/2002
M	A245	6,677,192	01/13/2004	Fitzgera	ld				07	7/16/2001
AT	A246	6,703,144	03/09/2004	Fitzgera	ld				03	3/18/2003
M	A247	6,703,688	03/09/2004	Fitzgera	ld				7/	16/2001
CAT	A248	6,737,670	05/18/2004	Cheng e	t al.				03	3/07/2003
AS	A249	6,750,130	01/07/2001	Fitzgera	ld				01	/07/2001
M	A250	2002/0084000	07/04/2002	Fitzgera	ld				12	2/17/2001
A	A251	2003/0215990	11/20/2003	Fitzgera	ld <i>et al</i> .				03	3/14/2003
055	A252	2004/0075149	04/22/2004	Fitzgera	ld et al.				07	7/23/2003
			FORI	EIGN PAT	ENT DOC	CUMENT	rs			
XAM. NIT.		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB. CLASS	FILING DATE	ABSTRAC ONLY	т	ENGLISH LANG (Y/N)
93	B45	61-141116	06/28/1986	JP				N		Y (abstract on
A	B46	2-210816	08/22/1990	JP				N		Y (abstract on
41	B47	3-036717	02/18/1991	JP				N		Y
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	•				FILING DATE:			March 17, 2004			
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EXAM. INIT.		DOCUMENT NUMBER	DATE	COUNTRY CODE	CLASS	SUB CLASS	FILING DATE	ABSTRAC ONLY	Т	ENGLISH LANG (Y/N)	
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EXAM. INIT.	ОТНЕ	ER DOCUMENTS	6: (Including	g Author, Ti	lle, Date, Re	levant Pa	ges, Place o	f Publication	1)		
US	C99	Grillot et al., "Ace Physics, Vol. 91,	-	-	-	_x Ga _{1-x}) _{0.5} Ir	n _{0.5} P heteros	structures," <u>Jo</u>	urna	al of Applied	
CAT	C100	Halsall et al., "Ele AlGalnP system,"							on o	n ordering in the	
USS	C101	Hsu et al., "Surface 1295	ce morpholog	gy of related (Ge _x Si _{1-x} films	s," <u>Appl. P</u>	hys. Lett., \	/ol. 61, No. 1	1 (1	992), pp. 1293-	
EXAMIN	ER	Crais a	20	npon	DATE	CONSIDI	ERED	12/28	<u> </u>	Ч	
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SHEET I OF I **FORM PTO - 1449** ATTY DOCKET NO.: ASC-025DVC1 APPLICANTS: Cheng et al. INFORMATION DISCLOSURE STATEMENT SERIAL NO.: 10/802,185 FILING DATE: March 17, 2004 JUN 0 9 2004 Not yet assigned 2913 GROUP: **U.S. PATENT DOCUMENTS** EXAM. DOCUMENT DATE NAME CLASS SUB FILING DATE IF INIT. NUMBER CLASS APPROPRIATE 5,572,043 11/5/1996 Shimizu et al. 05/15/1995 FOREIGN PATENT DOCUMENTS EXAM. DOCUMENT DATE COUNTRY CLASS **FILING** ABSTRACT ENGLISH INIT. CODE LANG (Y/N) NUMBER **CLASS** DATE ONLY OTHER ART, JOURNAL ARTICLES, ETC. EXAM. OTHER DOCUMENTS: (Including Author, Title, Date, Relevant Pages, Place of Publication) INIT. DATE CONSIDERED 12/28/04 Crain a Thous **EXAMINER**

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SHEET 1 OF 17 **FORM PTO - 1449** ATTY DOCKET NO.: ASC-025DVC1 INFORMATION DISCLOSURE STATEMENT APPLICANTS: Cheng et al. SERIAL NO.: 10/802,185 FILING DATE: March 17, 2004 Not yet assigned 2813 GROUP: U.S. PATENT DOCUMENTS DOCUMENT DATE NAME EXAM. CLASS SUB FILING DATE IF INIT. NUMBER CLASS APPROPRIATE 4,010,045 03/01/1977 Ruchrwein W 4,704,302 11/03/1987 Bruel et al. 4,710,788 12/01/1987 Dämbkes et al. 4,987,462 01/22/1991 Kim et al. **A5** 4,990,979 02/05/1991 Otto 4,997,776 03/05/1991 Harame et al. 05/07/1991 5,013,681 Godbey et al. **A8** 5,155,571 10/13/1992 Wang et al. A9 5,166,084 11/24/1992 Pfiester A10 5,177,583 01/05/1993 Endo et al. A11 5,202,284 04/13/1993 Kamins et al. A12 5,207,864 05/04/1993 Bhat et al. W1 AI3 5,208,182 05/04/1993 Narayan et al. A14 M 5,212,110 05/18/1993 Pfiester et al. AI5 5,221,413 06/22/1993 Brasen et al. A16 5,240,876 A 08/31/1993 Gaul et al. A17 5,241,197 08/31/1993 Murakami et al. A18 5,250,445 10/05/1993 Bean et al. A19 5,285,086 02/08/1994 Fitzgerald A20 5,291,439 03/01/1994 Kauffmann et al. A21 5,298,452 03/29/1994 Meyerson A22 5,310,451 05/10/1994 Tejwani et al. A23 5,316,958 05/31/1994 Meyerson 5,346,848 09/13/1994 Grupen-Shemansky et al. A25 5,374,564 12/20/1994 Bruel A26 5,399,522 03/21/1995 Ohori A27 5,413,679 05/09/1995 Godbey

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EXAMINER

								SHEET 2 OF 17
FORM	РТО –	1449		ΓA	TTY DOCKET NO.:	ASC-0	25DVC1	
INFOR	MATI	ON DISCLOSURE	STATEMENT	r AP	PPLICANTS:	Cheng	et al.	
				SE	RIAL NO.:	10/802	,185	
				FII	LING DATE:	March	17, 2004	
				GF	ROUP:	Not yet	assigned	2813
			U.S.	PATEN	T DOCUMENTS			
EXAM. INIT.		DOCUMENT NUMBER	DATE	NAME		CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
45	A28	5,424,243	06/13/1995	Takasak	ci	\ .		
CAT	A29	5,426,069	06/20/1995	Selvaku	ımar et al.			
ar	A30	5,426,316	06/20/1995	Moham	mad			
CAT	A31	5,442,205	08/15/1995	Brasen	et al.	\		
CAT	A32	5,461,243	10/24/1995	Ek et al				
CAT	-A33	5,461,250	10/24/1995	Burgha	rtz et al.			
AT	A34	5,462,883	10/31/1995	Dennar	d et al.			
IST	A35	5,476,813	12/19/1995	Naruse	-			
CAT	A36	5,479,033	12/26/1995	Baca et	al.		\	
UST	A37	5,484,664	01/16/1996	Kitahar	a et al.			
M	A38	5,523,243	06/04/1996	Moham	mad			\
CAT	A39	5,523,592	06/04/1996	Nakaga	wa et al.			
CAT	A40	5,534,713	07/09/1996	Ismail e	et al.			
CAI	A41	5,536,361	07/16/1996	Kondo	et al.			
IN	A42	5,540,785	07/30/1996	Dennan	d et al.			
CAS	A43	5,596,527	01/21/1997	Tomiok	ca et al.			
CAT	A44	5,617,351	04/01/1997	Bertin e	et al.			
18	A45	5,630,905	05/20/1997	Lynch e	et al.			
LST	A46	5,659,187	08/19/1997	Legoue	s et al.			
csy	A47	5,683,934	11/04/1997	Candela	aria			
(AT	A48	5,698,869	12/16/1997	Yoshim	ni et al.			
4	A49	5,714,777	02/03/1998	Ismail e	et al.			
CAT	A50	5,728,623	03/17/1998	Mori				
UST	A51	5,739,567	04/14/1998	Wong				
CAT	A52	5,759,898	06/02/1998	Ek et a	1.			
CAT	A53	5,777,347	07/07/1998	Bartelii	nk			
CAT	A54	5,786,612	07/28/1998	Otani e	t al.			
EXAM	INER	Crain a.	Dans.	w-	DATE CONSIDER	RED /2	2/28/	04

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FORM	PTO -	- 1449		•	ATTY DOCKET NO.:	ASC-0	25DVC1	
INFOR	MATI	ON DISCLOSURE	STATEMEN'	т	APPLICANTS:	Cheng	et al.	
					SERIAL NO.:	10/802	2,185	
					FILING DATE:	March	17, 2004	
					GROUP:	Not ye	t assigned	2813
			U.S.	PAT	ENT DOCUMENTS			
EXAM. INIT.		DOCUMENT NUMBER	DATE	NAM	IE .	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
45	A55	5,786,614	07/28/1998	Chi	uang et al.	1		
4	A56	5,792,679	08/11/1998	Nal	kato	\		
CAT	A57	5,808,344	09/15/1998	Ism	nail et al.			
UT	A58	5,847,419	12/08/1998	Ims	ni et al.			
(As	A59	5,863,830	01/26/1999	Bru	iel et al.			
(AT	A60	5,877,070	03/02/1999	God	esele et al.			
184	A61	5,882,987	03/16/1999	Sril	krishnan		V .	
IAT	A62	5,891,769	04/06/1999	Ho	ng et al.		1	
IAT	A63	5,906,708	05/25/1999	Rol	binson et al.			
CAT	A64	5,906,951	05/25/1999	Chi	u et al.			
(AT	A65	5,912,479	06/15/1999	Мо	ri et al.			
CAT	A66	5,943,560	08/24/1999	Chi	ang et al.			
(41	A67	5,963,817	10/05/1999	Chi	u et al.			
(AT	A68	5,966,622	10/12/1999	Lev	rine et al.			
CAT	A69	5,993,677	11/30/1999	Bia	sse et al.			
U	A70	5,998,807	12/07/1999	Lus	stig et al.		1	\
U	A71	6,013,134	01/11/2000	Chi	u et al.			\
CAT	A72	6,013,563	01/11/2000	Her	nley et al.			
WA	A73	6,020,252	02/01/2000	Ast	par et al.			
LAS	A74	6,033,974	03/07/2000	Her	nley et al.			T
UST	A75	6,033,995	03/07/2000	Mu	ller			
LAT	A76 、	6,058,044	05/02/2000	Sug	giura et al.			
(1)	A77	6,059,895	05/09/2000	Chi	u et al.			
CAT	A78	6,074,919	06/13/2000	Ga	rdner et al.			
CAT	A79	6,096,590	08/01/2000	Ch	an et al.			
CAT	A80	6,103,559	08/15/2000	Ga	rdner et al.			\
US	A81	6,103,597	08/15/2000	Ası	par et al.			
EXAM	INER	Craig a	1. Dany	n	DATE CONSIDER	ED L	128/	104

SHEET 4 OF 17

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FORM	PTO-	- 1449		:	ATTY DOCKET NO.:	ASC-0	25DVC1	
INFOR	ITAM	ON DISCLOSURE	STATEMEN	T	APPLICANTS:	Cheng	et al.	
					SERIAL NO.:	10/802	,185	
					FILING DATE:	March	17, 2004	
					GROUP:	Not ye	Lassigned 2	2313
			U.S.	PAT	TENT DOCUMENTS			
EXAM. INIT.		DOCUMENT NUMBER	DATE	NAM	1E	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
AT	A82	6,103,599	08/15/2000	Hei	nley et al.	\		
UT	A83	6,107,653	08/22/2000	Fitz	zgerald			
M	-A84	6,111,267	08/29/2000	Fise	cher et al.			
AT	-A85	6,117,750	09/12/2000	Ber	isahel et al.	1		
CAT	A86	6,130,453	10/10/2000	Me	i, et al.		1	
CAT	A87	6,133,799	10/17/2000	Fav	ors Jr., et al.		1	
(AT	A88	6,140,687	10/31/2000	Shi	momura et al.		·\	
UT	A89	6,143,636	11/07/2000	For	bes et al.			
AT	A90	6,153,495	11/28/2000	Kul	b et al.			
M	A91	6,154,475	11/28/2000	Sor	ef et al.			
LAT	A92	6,160,303	12/12/2000	Fatt	taruso			
IAT	A93	6,162,688	12/19/2000	Gar	dner et al.			
CAT	A94	6,162,705	12/19/2000	Her	nley et al.			
IAT	A95	6,184,111	02/06/2001	Her	nley et al.			
(AT	A96	6,190,998 B1	02/20/2001	Bru	el et al.		1	
LAT	A97	6,191,007	02/20/2001	Ma	tsui et al.			
CAT	A98	6,191,432	02/20/2001	Sug	iyama et al.			1
CAT	A99	6,194,722	02/27/2001	Hov	we et al.			
CAT	A100	6,204,529	03/20/2001	Lur	ng, et al.			
CAT	A101	6,207,977	03/27/2001	Aug	gusto			
4	A102	6,210,988	04/03/2001	Ho	we et al.			
CAT	A103	6,218,677	04/17/2001	Bro	ekaert			
CAT	A104	6,225,192 B1	05/01/2001	Asp	par et al.			
CAT	A105	6,232,138	05/15/2001	Fitz	gerald et al.			
AT	A106	6,235,567	05/22/2001	Hus	ang			
M	A107	6,242,324	06/05/2001	Kul	et al.			
CAT	A108	6,249,022	06/19/2001	Lin	, et al.			
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FORM	PTO -	1449		A	TTY DOCKET NO.:	ASC-0	25DVC1		
INFOR	MATI	ON DISCLOSURE	STATEMEN'	г А	PPLICANTS:	Cheng	et al.		
				SI	ERIAL NO.:	10/802	,185		
				FI	LING DATE:		March 17, 2004		
				G	ROUP:	2813			
			U.S. 1	PATEN	IT DOCUMENTS			•	
EXAM. INIT.		DOCUMENT NUMBER	DATE	NAME		CLASS	SUB CLASS	FILING DATE IF APPROPRIATE	
U	A109	6,251,751 BI	06/26/2001	Chu et	al.				
LAT	A110	6,251,755	06/26/2001	Furuka	wa ct al.				
IAT	A111	6,261,929	07/17/2001	Gehrke	et al.				
ar	A112	6,266,278	07/24/2001	Harari,	et al.				
UT	A113	6,271,551	08/07/2001	Schmit	z et al.				
ar	A114	6,271,726	08/07/2001	Fransis	et al.				
4	A115	6,290,804 B1	09/18/2001	Henley	et al.			02/20/1998	
UAT	A116	6,291,321	09/18/2001	Fitzger	ald			03/09/1999	
CAT	A117,	6,303,468 B1	10/16/2001	Aspar e	et al.			10/16/2001	
CAST	A118	6,313,016	11/06/2001	Kibbel	et al.			12/22/1999	
CAT	A119	6,316,301	11/13/2001	Kant				03/08/200	
UT	A120	6,323,108	11/27/2001	Kub et	al.			07/27/1999	
LAT	A121	6,326,667 B1	12/04/2001	Sugiya	ma et al.			09/08/2000	
CAT	A122	6,329,063	12/11/2001	Lo et a	1.			12/11/1998	
WI	A123	6,335,546	01/01/2002	Tsuda	et al.			07/30/1999	
(AF	A124	6,339,232	01/15/2002	Takagi				09/20/1999	
(AT	A125	6,344,417 B1	02/05/2002	Usenko)			08/08/2000	
UST	A126	6,346,459 B1	02/12/2002	Usenko	et al.			02/02/2000	
(AT	A127	6,350,993	02/26/2002	Chu et	al.			03/12/1999	
LAT	A128	6,352,909 B1	03/05/2002	Usenko)			05/26/2000	
CAT	A129	6,355,493 B1	03/12/2002	Usenko)			06/30/2000	
GT	A130	6,368,733	04/09/2002	Nishin	зда			08/05/1999	
CAT	A131	6,368,938 B1	04/09/2002	Usenko)			06/07/2000	
LAT	A132	6,369,438 B1	04/09/2002	Sugiya	ma et al.			12/22/2000	
UST	A133	6,372,356	04/16/2002	Thornt	on et al.			04/28/2000	
CAT	A134	6,372,593 B1	04/16/2002	Hattori	et al.			07/19/2000	
CAT	A135	6,372,609 B1	04/16/2002	Aga et	al.			10/08/1999	
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ATTY DOCKET NO.: ASC-025DVC1

APPLICANTS:

Cheng et al.

INFOR	ITAM	ON DISCLOSURI	E STATEMENT	r	APPLICANTS:	Cheng		
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					FILING DATE:		17, 2004	
		·			GROUP:	-Not-ye	t assigned	2813
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UST	A136	6,387,829 B1	05/14/2002	Use	nko et al.			04/06/2000
M	A137	6,391,740 B1	05/21/2002	Che	eung et al.			04/28/1999
AT	A138	6,399,970	06/04/2002	Kut	oo et al.			09/19/1997
AT	A139	6,403,975	06/11/2002	Bru	nner et al.			04/08/1997
AT	A140	6,407,406	06/18/2002	Tez	uka			06/29/1999
M	A141	6,410,371 B1	06/25/2002	Yu	et al.			02/26/2001
AI	A142	6,425,951	07/30/2002	Chu	et al.			08/06/1999
AT	A143	6,429,061	08/06/2002	Rin	1			07/26/2000
M	A144	6,445,016 B1	09/03/2002	Αл	et al.			02/28/2001
AT	A145	6,448,152 B1	09/10/2002	Hen	iley et al.			07/16/2001
AT	A146	6,455,397 B1	09/24/2002	Bel	ford			11/09/2000
AT	A147	6,458,672 B1	10/01/2002	Her	nley et al.			11/02/2000
M	A148	6,475,072 B1	11/05/2002	Can	aperi et al.			09/29/2000
CAT	A149	6,514,836 B2	02/04/2003	Bel	ford			06/04/2001
AT	A150	6,515,335 BI	02/04/2003	Chr	istiansen et al.			01/04/2002
AL	A151	6,521,041	02/18/2003	Wu	et al.			04/09/1999
A	A152	6,524,935 B1	02/25/2003	Can	aperi et al.			09/29/2000
AC	A153	6,534,381 B2	03/18/2003	Che	eung et al.			01/04/2000
AT	A154	6,555,839	04/29/2003		gerald et al.			05/16/2001
Ar	A155	6,573,126	06/03/2003		eng et al.			08/10/2001
AT	A156	6,583,015	06/24/2003		gerald et al.		ļ	08/06/2001
1	A157	6,583,437 B2	06/24/2003		runo et al.			03/19/2001
(AT	A158	6,593,191	07/15/2003		gerald			05/16/2001
AT	A159	6,593,625 B2	07/15/2003		istiansen et al.			04/03/2002
A	A160	6,596,610 B1	07/22/2003		wabara et al.			11/27/2000
À	A161	6,602,613	08/05/2003	Rin				01/17/2001
M	A162	6,603,156	08/05/2003	Fitz	gerald			03/31/2001
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INFORMATION DISCLOSURE STATEMENT

ATTY DOCKET NO.:

ASC-025DVC1

APPLICANTS:

Cheng et al.

SERIAL NO.:

10/802,185

FILING DATE:

March 17, 2004

GROUP:

Not yet assigned 2913

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EXAM. INIT.		DOCUMENT NUMBER	DATE	NAME		CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
AT	A163	6,607,948 B1	08/19/2003	Sugiya	ma et al.			08/24/2001
CAS	A164	6,624,047 B1	09/23/2003	Sakagu	chi et al.			02/01/2000
(A)	A165	6,624,478 B2	09/23/2003	Anders	on et al.			01/30/2002
As	A166	6,632,724 B2	10/14/2003	Henley	et al.			01/13/2000
LAT	A167	6,635,909 B2	10/21/2003	Clark e	t al.		<u> </u>	03/19/2002
W	A168	6,645,831 BI	11/11/2003	Shahee	n et al.			05/07/2002
(11	A169	6,649,492 B2	11/18/2003	Chu et	al.			02/11/2002
K	A170	6,656,271 B2	12/02/2003	Yoncha	ara et al.			12/03/1999
41	A171	6,664,169 B1	12/16/2003	Iwasak	et al.			06/05/2000
VSÍ	A172	6,677,183 B2	01/13/2004	Sakagu	chi et al.			01/31/2002
CAT	A173	6,680,240 B1	01/20/2004	Maszar	a			06/25/2002
CAR	A174	6,680,260 B2	01/20/2004	Akiyan	na et al.			09/17/2002
(AT	A175	6,690,043 B1	02/10/2004	Usuda	et al.			11/22/2000
M	A176	6,706,614 B1	03/16/2004	An et a	l.			05/15/2002
AT	A177	6,706,618 B2	03/16/2004	Takisav	va et al.			07/29/2002
CAT	A178	6,707,106 B1	03/16/2004	Wrister	s et al.			10/18/2002
CAT	A179	6,709,903 B2	03/23/2004	Christia	nsen et al.			04/30/2003
لير	A180	6,709,909 B2	03/23/2004	Mizuno	et al.			05/19/2003
AT	A181	6,713,326 B2	03/30/2004	Cheng	et al.			03/04/2003
AT	A182	2001/0003364	06/14/2001	Sugawa	ıra et al.			12/08/2000
US	A183	2001/0007789 A1	07/12/2001	Aspar e	t al.			02/26/2001
41	A184	2002/0043660	04/18/2002	Yamaz	aki et al.			06/25/2001
M	A185	2002/052084	05/02/2002	Fitzger	ald	_		05/16/2001
U	A186	2002/096717	07/25/2002	Chu et	al.			01/25/2001
W	A187	2002/0100942	08/01/2002	Fitzger	ald et al.			08/01/2002
(B)	A188	2002/0123167	09/05/2002	Fitzger	ald			07/16/2001
W	A189	2002/0123183	09/05/2002	Fitzger	ald			07/16/2001
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FORM PTO - 1449 -

INFORMATION DISCLOSURE STATEMENT

ATTY DOCKET NO.:

ASC-025DVC1

APPLICANTS:

Cheng et al.

SERIAL NO.:

10/802,185

FILING DATE:

March 17, 2004

GROUP:

Not yet assigned 2813

EXAM. INIT.		DOCUMENT NUMBER	DATE	NAME		CLASS	SUB CLASS	FILING DATE IF APPROPRIATE
UT	A190	2002/0123197	09/05/2002	Fitzgera	ild et al.			06/19/2001
CST	A191	2002/0125471	09/12/2002	Fitzgera	ild et al.			12/04/2001
6	A192	2002/0125497	09/12/2002	Fitzgera	ıld			07/16/2001
LAT	A193	2002/0168864	11/14/2002	Cheng 6	et al.			04/04/2002
AT	A194	2003/0003679	01/02/2003	Doyle e	t al.			06/29/2001
CAT	-A195	2003/0013305 A1	01/16/2003	Sugii et	al.			6/17/2002
(A=	A196	2003/0013323	01/16/2003	Hammo	nd et al.			6/14/2002
A	A197	2003/0025131	02/06/2003	Lee et a	1.			08/02/2002
UT	A198	2003/0034529	02/20/2003	Fitzgera	ld et al.			10/08/2002
UT	A199	2003/0057439	03/27/2003	Fitzgera	ıld			08/09/2002
CAT	A200	2003/0077867	04/04/2003	Fitzgera	ıld			07/16/2001
4	A201	2003/0102498	06/05/2003	Braithw	aite et al.			09/24/2002
4	A202	2003/0119280 A1	06/26/2003	Lee et a	1.			12/02/2002
a	A203	2003/0127646 A1	07/10/2003	Christia	nsen et al.			12/18/2002
4	A204	2003/0139000 A1	07/24/2003	Bedell e	et al.			01/23/2002
iAT	A205	2003/0157787 A1	08/21/2003	Murthy	et al.			02/21/2002
W	A206	2003/0160300 A1	08/28/2003	Takenal	ca et al.			02/24/2003
147	A2 07	2003/0168654 A1	09/11/2003	Cheng e	et al.			03/07/2003
UT	A208	2003/0178681 A1	09/25/2003	Clark et	al.			04/02/2003
CAT	A209	2003/0189229 A1	10/09/2003	Mouli				04/05/2002
ar	A210	2003/0199126 A1	10/23/2003	Chu et a	ıl.			04/23/2002
4	A211	2003/0201458 A1	10/30/2003	Clark et	al.			05/16/2003
var	A212	2003/0203600 A1	10/30/2003	Chu et a	al.			06/05/2003
M	A213	2003/0207127 A1	11/06/2003	Murthy	Murthy et al.			05/30/2003
UNT-	A214	2003/0218189 A1 ´	11/27/2003	Christiansen et al.				11/19/2002
CST	A215	2003/0219957 A1	11/27/2003	Kuwabara et al.				05/29/2003
CAT	A216	2003/0227036 A1	12/11/2003	Sugiyama et al. 02/21/2003			02/21/2003	
EXAM	EXAMINER Croix 9-22 DATE CONSIDERED 12/8/84							

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			U.S.	PATEN	IT E	OCUME	NTS					
EXAM. INIT.		DOCUMENT NUMBER	DATE	NAME				CLASS	SUB CLA	SS	1	DATE IF
WT	A217	2003/0227057	12/01/2003	Lochte	feld e	et al.					10/04/	/2002
ur	A218	2003/0230778 A1	12/18/2003	Park et	al.						01/30/	2003
VAT	A219	2003/0232467 A1	12/18/2003	Anders	on et	al.					05/29/	2003
IM	A220	2004/0005740	01/01/2004	Lochte	feld e	et al.					06/06/	/2003
iAC	A221	2004/0007724 A1	01/15/2004	Murthy	et a	l.					07/12/	2002
M	A222	2004/0009649 A1	01/15/2004	Kub et	al.						05/20/	/2003
UTT	A223	2004/0012037 A1	01/22/2004	Venkat	esan	et al.					07/18/	/2002
USK	A224	2004/0012075 A1	01/22/2004	Bedell	et al.					07/16		/2002
THE	A225	2004/0014304 A1	01/22/2004	Bhattac	chary	ya				07/18		/2002
AT	A226	2004/0018699 A1	01/29/2004	Boyd e	t al.					07/24/		/2002
iAi	A227	2004/0031979	02/19/2004	Lochte	feld (et al.				06/06/		/2003
UR	A228	2004/0031990 A1	02/19/2004	Jin et a	1.					08/16		/2002
CAT	A229	2004/0041174 A1	03/04/2004	Okihar	8		_				03/21	/2003
4	_ A230	2004/0041210 A1	03/04/2004	Mouli							09/02	/2003
IN	A231	2004/0048091 A1	03/11/2004	Sato et	al.						09/04	/2003
ist	A232	2004/0048454 A1	03/11/2004	Sakagu	chi						09/04	/2003
LAT	A233	2004/0051140 A1	03/18/2004	Bhatta	chary	⁄ya					09/12	/2002
ist	A234	2004/0053477 A1	03/18/2004	Ghysel	en et	al.					07/09	/2003
			FOREI	GN PAT	ΓEN	T DOCU	MENT	S				
EXAM. INIT.		DOCUMENT NUMBER	DATE	COUNT	RY	CLASS	SUB CLASS	FILIN DATI		ABSTI		ENGLISH LANG (Y/N)
US.	BI	41 01 167	07/23/1992	DE			Carros	JA.		No		No No
CAS	B2	0 514 018	11/19/1992	EP				_		No	<u></u>	Yes
41	B3	0 587 520	03/16/1994							No		Yes
14	` B4	0 683 522	11/22/1995							No		Yes
45	B5	0 828 296	03/11/1998					-		No		Yes
600	B6	0 829 908	03/18/1998	EP						No		Yes
CAT	B7	0 838 858	04/29/1998	EP						No		No
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FORM PTO – 1449

INFORMATION DISCLOSURE STATEMENT

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APPLICANTS:

Cheng et al.

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EXAM. INIT.		DOCUMENT NUMBER	DATE	COD	NTRY E	CLAS S	SUB CLASS	FILING DATE	ABSTRACT ONLY	ENGLISH LANG (Y/N)
M	B8	1 020 900	07/19/2000	EP					No	Yes
AT	B9	1 174 928	01/23/2002	EP					No	Yes
UT	B10	2 342 777	04/19/2000	GB					Yes	Yes
Ar-	BII	4-307974	10/30/1992	JP					No	No
CAT	B12	5-166724	07/03/1993	JP					No	Abstract Only
AT	B13	6-177046	06/24/1994	JP					No	Abstract Only
M	B14	7-106446	04/21/1995	JP					No	No
M	B15	7-240372	09/12/1995	JP					No	Abstract Only
IAT	B16	10-270685	10/09/1998	JP					No	Yes
CAT	B17	11-233744	08/27/1999	JP					No	No
(M	B18	2000-021783	01/21/2000	JP					No	Yes
CAST	B19	2000-31491	01/28/2000	JP					No	No
45	B20	2001319935	05/11/2000	JP					Yes	Yes
LAT	B21	2002-076334	03/15/2002	JP					No	Yes
CAT	B22	2002-164520	06/07/2002	JP					No	Yes
CAT	B23	2002-289533	10/04/2002	JP					No	Yes
COST	B24	WO 98/59365	12/30/1998	PCT					No	Yes
CAT	B25	WO 99/53539	10/21/1999	PCT					No	Yes
CAT	B26	WO 00/48239	08/17/2000	PCT					No	Yes
AT	B27	WO 01/54202	07/26/2001	PCT					No	Yes
AT	B28	WO 01/99169A2	12/27/2001	PCT					No	Yes
(AT	B29	WO 02/15244 A2	02/21/2002	PCT					No	Yes
(AF	B30	WO 02/27783 A1	04/04/2002	PCT					No	Yes
AT	-B31	WO 02/071495A1	09/12/2002	PCT					No	Yes
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EXAM. INIT.		DOCUMENT NUMBER	DATE	COD	NTRY E	CLAS S	SUB CLASS	FILING DATE	ABSTRACT ONLY	ENGLISH LANG (Y/N)
GH	B32	WO 02/082514 A1	10/17/2002	PCT					No	Yes
UT	B33	WO 00/54338	09/14/2000	wo					No	Yes
CAT	B34	WO 01/022482	03/29/2001	wo					No	Yes
Ut	B35	WO 01/93338	12/06/2001	wo					No	Yes
UT	B36	WO 02/13262	02/14/2002	wo					No	Yes
(AT	B37	WO 02/47168	06/13/2002	wo					No	Yes
1	B38	WO 02/071488	09/12/2002	wo					No	Yes
IAT	B39	WO 02/071491	09/12/2002	wo					No	Yes
IAT	B40	WO 04/006311 A2	01/15/2004	wo				07/09/2003		YES
LAT	B41	WO 04/006326 A1	01/15/2004	wo				07/09/2003		YES
UT	B42	WO 04/006327 A2	01/15/2004	wo				07/09/2003		YES
(AT	B43	WO 04/019403 A2	03/04/2004	wo				08/26/2003		YES
GT	B44	WO 04/019404 A2	03/04/2004	wo	,,			08/26/2003		YES
			OTHER AI	RT, JO	OURN	AL AR	ICLES,	ETC.		<u>"</u>
EXAM. INIT.	ОТНЕ	ER DOCUMENTS:	(Including Au	thor, T	itle, Da	te, Releva	nt Pages, l	Place of Public	ation)	
GAT	C1 "2 Bit/Cell EEPROM Cell Using Band to Band Tunneling for Data Read-Out," IBM Technical Disclosure Bulletin, Vol. 35, No. 4B (September 1992) pp. 136-140.									
(AT.	C2	Armstrong et al., "Design of Si/SiGe Heterojunction Complementary Metal-Oxide-Semiconductor Transistors," IEDM Technical Digest (1995) pp. 761-764.								
UT	C3	Armstrong, "Technology for SiGe Heterostructure-Based CMOS Devices", Ph.D Thesis, Massachusetts Institute of Technology (1999) pp. 1-154.								
67	C4	Augusto et al., "Proposal for a New Process Flow for the Fabrication of Silicon-Based Complementary MOD-MOSFETs without Ion Implantation," Thin Solid Films, Vol. 294, No. 1-2 (1997) pp. 254-258.								
CAT	-€5	Barradas et al., "R channels for HM0							in, high Ge cont	ent SiGe
EXAMI	NER	Craiga.	26_		D.	ATE CO	NSIDER	ED (2)	48/ 44	
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INFORMATION	I DISCLOSURE STATEMENT	APPLICANTS:	Cheng et al.			
		SERIAL NO.:	10/802,185			
		FILING DATE:	March 17, 2004			
		GROUP:	Not yet assigned 2-813			
	OTHER ART, J	OURNAL ARTICLES,	ETC.			
EXAM. OTHER INIT.	DOCUMENTS: (Including Author, 7	itle, Date, Relevant Pages, l	Place of Publication)			
CAT C6			ion Micromachining," Proceedings of the al Systems (MEMs) (January 17-21, 1999) pp.			
AT C7	Bouillon et al., "Search for the optimal c IEEE (1996) pp. 21.2.1-21.2.4.	hannel architecture for 0.18/0	.12 µm bulk CMOS Experimental study,"			
(A) C8	Bruel et al., "@SMART CUT: A Promis SOI Conference (October 1995) pp. 178	-	ology," Proceedings 1995 IEEE International			
(A) C9	Bruel, "Silicon on Insulator Material Tec 1202.	chnology," <u>Electronic Letters</u> ,	Vol. 13, No. 14 (July 6, 1995) pp. 1201-			
(AT	84, No. 10 (November 15, 1998) pp. 55	97-5602.	ubstrates," <u>Journal of Applied Physics,</u> Vol.			
AT CII	Burghartz et al., "Microwave Inductors a IEEE Transactions on Microwave Theo	nd Capacitors in Standard M ry and Techniques, Vol. 44, N	ultilevel Interconnect Silicon Technology", No. 1 (January 1996) pp. 100-104.			
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C13	Carlin et al., "High Efficiency GaAs-on- pp. 1006-1011	Si Solar Cells with High Voc	Using Graded GeSi Buffers," <u>IEEE</u> (2000)			
UST C14	Chang et al., "Selective Etching of SiGe (January 1991) pp. 202-204.	Si Heterostructures," <u>Journal</u>	of the Electrochemical Society, No. 1			
CI5	Cheng et al., "Electron Mobility Enhanc Substrates," <u>IEEE Electron Device Lette</u>		ETs Fabricated on SiGe-on-Insulator (SGOI)) pp. 321-323.			
C16	Cheng et al., "Relaxed Silicon-Germaniu Materials, Vol. 30, No. 12 (2001) pp. L		ayer Transfer," <u>Journal of Electronic</u>			
Var	Vacuum Science and Technology A, Vo	ol. 12, No. 4 (July/August 199				
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C19	Currie et al., "Controlling Threading Dislocation in Ge on Si Using Graded SiGe Layers and Chemical-Mechanical Polishing," vol. 72 No. 14 (April 6, 1998) pp. 1718-1720.					
C20	Eaglesham et al., "Dislocation-Free Stranski-Krastanow Growth of Ge on Si(100)," Physical Review Letters, Vol. 64, No. 16 (April 16, 1990) pp. 1943-1946.					
C21	Feijoo et al., "Epitaxial Si-Ge Etch Stop Layers with Ethylene Diamine Pyrocatechol for Bonded and Etchback Silicon-on-Insulator," <u>Journal of Electronic Materials</u> , Vol. 23, No. 6 (June 1994) pp. 493-496.					
C22	Fischetti et al., "Band structure, deformation potentials, and carrier mobility in strained Si, Ge, and SiGe alloys," J. Appl. Phys., Vol. 80, No. 4 (August 15, 1996) pp. 2234-2252.					
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INFOR	MATIO	ON DISCLOSURE STATEMENT	APPLICANTS:	Cheng et al.			
			SERIAL NO.:	10/802,185			
			FILING DATE:	March 17, 2004			
			GROUP:	-Not yet assigned 2813			
		OTHER ART, J	OURNAL ARTICLES,	ETC.			
EXAM.	ОТНЕ	R DOCUMENTS: (Including Author, 1					
INIT.		•	_	,			
GAP	C23	Fischetti, "Long-range Coulomb interact structures," <u>Journal of Applied Physics</u> ,		II. Effective electron mobility in thin-oxide 2001) pp. 1232-1250.			
UAF	C24	Fitzgerald et al., "Dislocation dynamics Engineering B67 (1999) pp. 53-61.	in relaxed graded composition	n semiconductors," <u>Materials Science and</u>			
AT	C25	Fitzgerald et al., "Relaxed Ge _x Si _{1-x} struct electron gases in Si," AT&T Bell Labor 1807-1819.	-	h Si and high mobility two-dimensional 4 (1992) <u>American Vacuum Society</u> , pp.			
CAF	C26	Fitzgerald et al., "Totally Relaxed Ge _x Si Substrates," <u>Applied Physics Letters</u> , V		2			
U	C27	Garone et al., "Silicon vapor phase epital Vol. 56, No. 13 (March 26, 1990) pp. 1		resence of germane," Applied Physics Letters,			
LAT	C28	Godbey et al., (1990) "Fabrication of Bo Etch Stop," <u>Journal of the Electrical So</u>		ulator Using a Strained SI _{0.7} GE _{0.3} Layer as an ber 1990) pp. 3219-3223.			
AT	C29	Gray and Meyer, "Phase-Locked Loops"	, Analysis and Design of Ana	log Integrated Circuits (1984) pp. 605-632.			
(AF	C30	Grützmacher et al., "Ge segregation in S growth atmosphere," Applied Physics L		s dependence on deposition technique and mber 1, 1993) pp. 2531-2533.			
(A)	C31	Hackbarth et al., "Alternatives to thick N (July 2000) pp. 148-151.	MBE-grown relaxed SiGe buff	fers," Thin Solid Films, Vol. 369, No. 1-2			
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			SERIAL NO.:	10/802,185			
			FILING DATE:	March 17, 2004			
			GROUP:	Not yet assigned 2813			
		OTHER ART, J	OURNAL ARTICLES,	ETC.			
EXAM.	ОТНЕ	R DOCUMENTS: (Including Author,					
INIT.	01.112	`					
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ST	C41	Ishikawa et al., "Creation of Si-Ge-based IEEE International SQI Conference (Oc	-	nergy oxygen implantation," <u>Proceedings 1997</u>			
M	C42	7 (August 16, 1999) pp. 983-985.		Si(001)," <u>Applied Physics Letters</u> , Vol. 75, No.			
ST	C43	Ismail et al., "Modulation-doped n-type (September 5, 1994) pp. 1248-1250.					
UST	C44	Ismail, "Si/SiGe High-Speed Field-Effec 1995) pp. 20.1.1-20.1.4.	rt Transistors," <u>Electron Devi</u>	ces Meeting, Washington, D.C. (December 10,			
41	C45	Kearney et al., "The effect of alloy scatte Technol., Vol. 13 (1998) pp. 174-180.	ering on the mobility of holes	in a Si _{l-x} Ge _x quantum well," <u>Semicond. Sci</u>			
ST	C46	Kim et al., "A Fully Integrated 1.9-GHz Vol. 8, No. 8 (August 1998) pp. 293-29		," IEEE Microwaye and Guided Wave Letters,			
4	C47	Koester et al., "Extremely High Transco Electron Device Letters, Vol. 21, No. 3		DDFET's Grown by UHV-CVD," <u>IEEE</u>			
LAT	C48	1541-1547.		te Electronics, Vol. 41, No. 10 (1997), pp.			
CST	C49	König et al., "p-Type Ge-Channel MOD Electron Device Letters, Vol. 14, No. 4	FET's with High Transcondu (April 1993) pp. 205-207.	ctance Grown on Si Substrates," IEEE			
CAT	C50	König et al., "SiGe HBTs and HFETs,"	Solid-State Electronics, Vol.	38, No. 9 (1995) pp. 1595-1602.			
Car	C51	Kummer et al., "Low energy plasma enh (2002) pp. 288-295.	anced chemical vapor deposit	tion," Materials Science and Engineering B89			
41	C52	Kuznetsov et al., "Technology for high- Vac. Sci. Technol., B 13(6) (November		modulation-doped field-effect transistors," <u>J.</u> 896.			
CAT	C53	Langdo et al., (2002) "Preparation of Novel SiGe-free Strained Si on Insulator Substrates" <u>IEEE International SOI</u> <u>Conference</u> , pages 211-212 (XP002263057)					
Y	C54	Larson, "Integrated Circuit Technology Options for RFIC's - Present Status and Future Directions", IEEE Journal of Solid-State Circuits, Vol. 33, No. 3, March 1998, pp. 387-399.					
47	C55	Lee et al., "CMOS RF Integrated Circuits at 5 GHz and Beyond", Proceedings of the IEEE, Vol. 88, No. 10 (October 2000) pp. 1560-1571.					
43	C56	virtual substrates," Applied Physics Letters, Vol. 79, No. 20 (November 12, 2001) pp. 3344-3346.					
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